

Form PTO 1449 U.S. DEPARTMENT OF COMMERCE
(Modified) PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.

8733.215.00

08/671,376

APPLICANT

Tieer GU et al.

FILING DATE

June 27, 1996

GROUP

2822

LIST OF REFERENCES CITED BY APPLICANT
(Use Several Sheets if Necessary)

Date: February 5, 2001

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>QMD</i>	AA	6,100,954	08/08/00	Kim et al.	349	138	
<i>QMD</i>	AB	4,636,038	01/1987	Kitahara et al.	350	339	
<i>QMD</i>	AC	4,943,838	07/1990	Ukai	257	410	
<i>QMD</i>	AD	5,072,262	12/1991	Uekita et al.	257	410	
<i>QMD</i>	AE	5,229,644	07/1993	Wakai et al.	257	749	
<i>QMD</i>	AF	5,246,782	09/1993	Kennedy et al.	428	421	
<i>QMD</i>	AG	5,294,820	03/1994	Gemma et al.	257	324	
<i>QMD</i>	AH	5,486,493	01/1996	Jeng	437	195	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES	TRANSLATION NO
<i>QMD</i>	AI	63-279228	11/1988	JAPAN		
<i>QMD</i>	AJ	63-289965	11/1988	JAPAN		
<i>QMD</i>	AK	04-068318	03/1992	JAPAN		
<i>QMD</i>	AL	04-163528	06/1992	JAPAN		
<i>QMD</i>	AM	05-203936	08/1993	JAPAN		

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>QMD</i>	AN	M.J. Radler et al., Cyclotene™ Advanced Electronics Resins for High-Aperture AMLCD Applications, SID 96 APPLICATIONS DIGEST, pp. 33-36 (1996).
<i>QMD</i>	AO	Eric P. Finchem et al., A Multi-Level High Density Interconnect Process Designed & Developed for Manufacturability, TriQuint Semiconductor, Inc., Beaverton, OR, USA
<i>QMD</i>	AP	M.J. Radler et al., Benzocyclobutene Dielectric Resins for Flat Panel Display Applications, Proceedings of the 3 rd Annual Display Manufacturing Technology Conference, pp: 123-4, 1996 (Conference date: February 6-8, 1996)

EXAMINER

DATE CONSIDERED

2/28/03

*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

**English-language abstract provided.

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LIST OF REFERENCES CITED BY APPLICANT (Use Several Sheets if Necessary) Date: <u>January 29, 2001</u>				APPLICANT Tieer GU et al.			
				FILING DATE June 27, 1996		GROUP 2822	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JMD</i>	BA	5,585,951	12/1996	Noda et al.	349	122	
<i>JMD</i>	BB	5,591,676	01/1997	Hughes et al.	438	702	
<i>JMD</i>	BC	5,641,974	06/1997	Den Boer et al.	257	59	
<i>JMD</i>	BD	5,675,187	10/1997	Numata et al.	257	758	
<i>JMD</i>	BE	5,721,596	02/1998	Kochi	349	2	
<i>JMD</i>	BF	5,721,601	02/1998	Yamaji et al.	349	138	
<i>JMD</i>	BG	5,821,621	10/1998	Jeng	257	759	
<i>JMD</i>	BH	6,038,008	03/14/2000	Kim et al.	349	138	08/964,914 - 11/05/1997
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
<i>JMD</i>	BI	0-536-898 A1	04/1993	EUROPEAN PATENT OFFICE (In English)			
<i>JMD</i>	BJ	0-589-478 A2	03/1994	EUROPEAN PATENT OFFICE (In English)			
<i>JMD</i>	BK	0-589-478 A3	03/1994	EUROPEAN PATENT OFFICE (In English)			
<i>JMD</i>	BL	0-486-047 A2	05/1992	EUROPEAN PATENT OFFICE (In English)			
<i>JMD</i>	BM	0-486-047 A3	05/1992	EUROPEAN PATENT OFFICE (In English)			
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>JMD</i>	BN	Stanley Wolf et al., <i>Silicon Processing For The VLSI Era</i> , Vol. 1, Process Technology, Lattice Press, Sunset Beach, CA., 1986					
<i>JMD</i>	BO	Tadanori Shimoto et al. <i>High Density Multilayer Substrate Using Benzocyclobutene Dielectric</i> , IMC 1992 Proceedings, Yokohama, June 3-5, 1992, pp: 325-30					
<i>JMD</i>	BP	Willem den BOER et al., <i>High Aperture TFT LCD using Polymer Interlevel Dielectric</i> , OIS Optical Imaging Systems, Inc., Northville, MI, USA					
EXAMINER: <i>Janifer M. Obo</i>					DATE CONSIDERED <u>2/28/03</u>		
<p>*EXAMINER: Initial reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p> <p>**English-language abstract provided.</p>							

Form PTO 1449 U.S. DEPARTMENT OF COMMERCE (Modified) PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT (Use Several Sheets if Necessary) Date: <u>January 29, 2001</u>	ATTY. DOCKET 8733.215.00	08/671,376 APPLICANT Tieer GU et al. FILING DATE June 27, 1996 GROUP 2822
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EXAMINER INITIAL	CA	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>QMD</i>	CA	4,431,272	02/1984	Yazawa et al.	350	336	
<i>QMD</i>	CB	4,451,525	05/1984	Kawazoe et al.	428	213	
<i>QMD</i>	CC	5,408,345	04/1995	Mitsui et al.	349	42	
<i>QMD</i>	CD	5,411,629	05/1995	Warfield	216	34	
<i>QMD</i>	CE	5,500,750	03/1996	Kanbe et al.	349	42	
<i>QMD</i>	CF	5,600,458	02/1997	Okano et al.	349	44	
<i>QMD</i>	CG	5,724,111	03/1998	Mizobata et al.	349	113	
<i>QMD</i>	CH	5,844,647	12/1998	Maruno et al.	349	138	

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		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES	NO
<i>QMD</i>	CI	0-616-241 A2	09/1994	EUROPEAN PATENT OFFICE (In English)		
<i>QMD</i>	CJ	0-714-140 A1	05/1996	EUROPEAN PATENT OFFICE (In English)		
<i>QMD</i>	CK	2-311-653	10/1997	UNITED KINGDOM (In English)		
<i>QMD</i>	CL	41-40-180 A1	12/1992	DENMARK		
<i>QMD</i>	CM	4-257826A	09/1992	JAPAN (English Abstract only)		

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>QMD</i>	CN	M.W. Friends, <i>Determination of Dielectric Constant for Fuji Clear</i> , 3/7/1996, pp:1-2, including Table
<i>QMD</i>	CO	Willem den BOER, <i>A Two-Diode Pixel Circuit and Addressing Method for MIM LCDs</i> , OIS Optical Systems, Inc., Northville, MI, USA
<i>QMD</i>	CP	Tech Notes, Advanced Electronics Resins, <i>Processing Guide for Photo-Imageable BCB</i> , Dow Chemical Co., pp: 1-4

EXAMINER <i>James M. Ho</i>	DATE CONSIDERED <u>2/28/03</u>
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U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JMD</i>	DA	5,177,588	01/05/1993	li et al.	257	640	
<i>JMD</i>	DB	5,045,905	09/03/1991	Motai et al.	357	207	
<i>JMD</i>	DC	5,281,546	01/25/1994	Possin et al.	437	40	
<i>JMD</i>	DD	5,003,356	03/26/1991	Wakai et al.	357	4	
<i>JMD</i>	DE	5,847,720	12/08/1998	Dunand	347	1	
<i>JMD</i>	DF	5,576,630	11/19/1996	Fujita	324	760	
<i>JMD</i>	DD	5,920,084	07/06/1999	Gu et al.	257	59	
<i>JMD</i>	DH	5,780,874	07/14/1998	Kudo	257	77	

FOREIGN PATENT DOCUMENTS					
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO
<i>JMD</i>	DI	10-133165	05/1998	JAPAN	
	DJ				
	DK				
	DL				
	DM				

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)		
<i>JMD</i>	DN	Michael Schier, <i>Reactive Ion Etching of Benzocyclobutene Using a Silicon Nitride Dielectric Etch Mask</i> , J. Electrochem. Soc., Vol. 142, No. 9, September 1995, pp: 3238-40
<i>JMD</i>	DO	Donald Peretrie, et al., <i>Benzocyclobutene as a Planarization Resin for Flat Panel Displays</i> , SPIE Vo., 1965, Liquid Crystal Materials, Device, and Applications (1992), pp: 331-7
	DP	

EXAMINER <i>Jennifer M. Dola</i>	DATE CONSIDERED <u>2/28/03</u>
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JMD</i>	EA	5,477,359	12/19/1995	Okazaki	359	77	
<i>JMD</i>	EB	5,287,208	02/15/1994	Shimoto et al.	359	75	
<i>JMD</i>	EC	5,994,721	11/30/1999	Zhong et al.	257	89	
	ED						
	EE						
	EF						
	ED						
	EH						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
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	EJ					
	EK					
	EL					
	EM					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER	<i>Jennifer M. Dole</i>	DATE CONSIDERED	<i>4/28/03</i>
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Notice of References Cited

Application No.
08/671,376

Gu et al

Examiner
Michael Trinh

Group Art Unit
2822

Page 1 of 1

U.S. PATENT DOCUMENTS

	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
A	5,477,359	12/19/95	Okazaki	359	77
B	5,559,055	9/24/96	Chang et al	438	586
C	5,780,874	7/14/98	Kudo	257	642
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
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Notice of References Cited

Application No.
08/671,376

Gu et al

Examiner
Michael Trinh

Group Art Unit
2813

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U.S. PATENT DOCUMENTS

	D CUMENT NO.	DATE	NAME	CLASS	SUBCLASS
<i>Handwritten: A</i>	5,466,535	11/14/95	Higgins et al	428	483
<i>Handwritten: B</i>	5,477,380	12/19/95	Sunohara et al	349	132
<i>Handwritten: C</i>	5,585,951	12/17/96	Noda et al	349	122
D					
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FOREIGN PATENT DOCUMENTS

	DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS
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NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
<i>Handwritten: U</i>	Wolf et al, "Silicon Processing for the VLSI Era", vol 1, pp 407-408,418-421,428-429	1986
V		
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Handwritten signature: Jennifer M. Dole 2/28/03

Sheet 1 of 1Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Sheet 1 of 1

Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Section 2. Form PTO - 1449 (Modified)

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE
(Modified) PATENT AND TRADEMARK OFFICE

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

(Use several sheets if necessary)

(37 CFR 1.98(b))

ATTY. DOCKET NO.

12190.293

SERIAL NO.

08/671,376

APPLICANT

den BOER, ET. AL.

FILING DATE

6/27/96

GROUP

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>QMN</i>	5 0 0 3 3 5 6	3/91	WAKAI, ET. AL.			
<i>QMN</i>	5 3 0 2 9 8 7	4/94	KANEMORI, ET. AL.			
<i>QMN</i>	5 4 1 4 2 7 8	5/95	KOBAYASHI, ET. AL.			
<i>QMN</i>	5 4 6 3 2 3 0	10/95	NEGOTO, ET. AL.			
<i>QMN</i>	5 4 6 3 4 8 4	10/95	BRODY			
<i>QMN</i>	5 5 2 8 2 0 9	6/96	MACDONALD, ET. AL.			

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

		DOCUMENT NUMBER						PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUBCLASS	TRANSLATION	
												YES	NO

OTHER DOCUMENTS (Including Author, Title, Date**, Relevant Pages, Place of Publication***)

EXAMINER

Quayle M. Dot

DATE CONSIDERED

2/29/03

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JC879 U.S. PTO
10/052767
01/23/02

Section 2. Form PTO - 1449 (Modified)

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE (Modified) PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary) (37 CFR 1.98(b))	ATTY. DOCKET NO. 12190.293	SERIAL NO. 08/671,376
	APPLICANT den BOER, ET. AL.	
	FILING DATE 6/27/96	GROUP

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date*, Relevant Pages, Place of Publication***)

JMN		"OPTIMISATION OF VERY SMALL PITCH ACTIVE MATRIX LCD FOR PROJECTION" BY VIGNOLLE, ET. AL., IBEE, 1991
JMN		"A HIGH-APERTURE-RATIO 3-IN.-DIAGONAL VGA A-SI LIGHT VALVE WITH PIXEL/DATA AND PIXEL/GATE LINES OVERLAPPING" BY SAKAMOTO, ET. AL. SID 1996 DIGEST
JMN		"HIGH APERTURE AND FAULT-TOLERANT PIXEL STRUCTURE FOR TFT-LCDs" BY KIM, ET. AL., SID 1995 DIGEST

EXAMINER	DATE CONSIDERED
<i>Amos M. Deter</i>	<i>2/28/03</i>

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